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Optimization of defect compensation for extreme ultraviolet lithography mask by covariance-matrix-adaption evolution strategy (Erratum)

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This article [*J. Micro/Nanolith. MEMS MOEMS* **17**(4), 043505 (2018), doi: 10.1117/1.JMM.17.4.043505] was originally published online on 3 December 2018 with an error in the caption of Fig. 25. The figure caption appeared incorrectly as "Convergence curves of GA and CMA-ES for optimization of larger and complex mask pattern." It has been corrected to: "Convergence curves of CMA-ES for optimization of larger and complex mask pattern."

Also, there was an error in the parameter settings listed in Sec. 3.5. The sentence: "As shown by the purple circle in Fig. 24, the defect is positioned near a corner of an S-shaped pattern feature, and the defect parameters, x_{pos}, y_{pos}, h_{top}, w_{top}, h_{bot}, and w_{bot}, are set as 50, 65, 9, 27, 8, and 35, respectively" has been corrected to: "As shown by the purple circle in Fig. 24, the defect is positioned near a corner of an S-shaped pattern feature, and the defect parameters, x_{pos}, y_{pos}, h_{top}, w_{top}, h_{bot}, and w_{bot}, are set as 36, 108, 8, 35, 50, 65, respectively."

All online versions of the article were corrected on 21 February 2019.

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